



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of:

KOZAWA et al.

Attorney Docket No: 100021-00065

Application No. 10/005,347

Art Unit: 1712

Filed: December 7, 2001

Examiner: K. Peng

For: SILICON-CONTAINING POLYMER, PROCESS FOR ITS PRODUCTION,
RESIST COPOSITION EMPLOYING IT, PATTERN-FORMING METHOD AND
ELECTRONIC DEVICE FABRICATION METHOD

AMENDMENT AFTER ALLOWANCE 37 CFR § 1.312

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

September 21, 2004

Sir:

Prior to issuance of the above-identified application, please amend the
application as follows: